

TSMC-01-1094

January 14, 2004

To: Commissioner for Patents
P.O.Box 1450
Alexandria, VA 22313-1450

Fr: George O. Saile, Reg. No. 19,572
28 Davis Avenue
Poughkeepsie, N.Y. 12603

Subject: | Serial No. 10/694,426 10/27/03 |

Fei-Gwo Tsai et al.

METHOD OF A FLOATING PATTERN
LOADING SYSTEM IN MASK DRY-ETCHING
CRITICAL DIMENSION CONTROL

INFORMATION DISCLOSURE STATEMENT

Enclosed is Form PTO-1449, Information Disclosure Citation
In An Application.


The following Patents and/or Publications are submitted to
comply with the duty of disclosure under CFR 1.97-1.99 and
37 CFR 1.56.

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being
deposited with the United States Postal Service as first class
mail in an envelope addressed to: Commissioner for Patents,
P.O. Box 1450, Alexandria, VA 22313-1450, on January 27, 2004.

Stephen B. Ackerman, Reg.# 37761

Signature/Date

 1/27/04

TSMC-01-1094

U.S. Patent 6,281,049 to Lee, "Semiconductor Device Mask and Method for Forming the Same," discloses a mask process with dummy patterns involving macro loading.

U.S. Patent 5,899,706 to Kluwe et al., "Method of Reducing Loading Variation During Etch Processing," discloses a process to reduce loading variation during etching.

U.S. Patent 5,278,105 to Eden et al., "Semiconductor Device with Dummy Features in Active Layers," discloses a method for a device with dummy lines in active layers.

Sincerely,

A handwritten signature in black ink, appearing to read 'SBA', with a long horizontal flourish extending to the right.

Stephen B. Ackerman,
Reg. No. 37761

Form PTO-1449

INFORMATION DISCLOSURE CITATION IN AN APPLICATION

(Use several sheets if necessary)

Docket Number (Optional)

TSMC-01-1094

Application Number

10/694,426

Applicant

Fei - Gwo T sai et al.

Filing Date

10/27/03

Group Art Unit

U. S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	ALNO DATE IF APPROPRIATE
	62810498	8/28/01	Lee	438	129	12/23/98
	58997065	5/4/99	Kluwe et al.	438	129	6/30/97
	52781051	1/11/94	Eden et al.	437	250	8/19/92

FOREIGN PATENT DOCUMENTS

DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
					YES	NO

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

EXAMINER

DATE CONSIDERED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.